

# Resource Summary Report

Generated by [RRID](#) on Aug 5, 2026

## Oxford: PlasmaPro 100 Nano Plasma Technology

RRID:SCR\_020384

Type: Tool

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### Proper Citation

Oxford: PlasmaPro 100 Nano Plasma Technology (RRID:SCR\_020384)

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### Resource Information

**URL:** <https://plasma.oxinst.com/products/cvd/plasmapro-100-nano>

**Proper Citation:** Oxford: PlasmaPro 100 Nano Plasma Technology (RRID:SCR\_020384)

**Description:** Chemical Vapour Deposition and PECVD tools for growth of 1D and 2D nanomaterials and heterostructures. PlasmaPro 100 Nano delivers performance growth of nanomaterials with in situ catalyst activation and process control, with flexible temperatures up to 1,200 degrees C.

**Resource Type:** instrument resource

**Keywords:** Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

**Availability:** Commercially available

**Resource Name:** Oxford: PlasmaPro 100 Nano Plasma Technology

**Resource ID:** SCR\_020384

**Alternate IDs:** Model\_Number\_100\_Nano

**Record Creation Time:** 20220129T080350+0000

**Record Last Update:** 20260801T190656+0000

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### Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 100 Nano Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 100 Nano Plasma Technology.

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### Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.